



#42877

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Michael Weber-Grabau et al. PATENT APPLICATION

Serial No.: 09/927,102

Group Art Unit: 2877

Filed: August 10, 2001

Examiner:

For: OPTICAL CRITICAL DIMENSION METROLOGY SYSTEM

INTEGRATED INTO SEMICONDUCTOR WAFER PROCESS TOOL

Information Disclosure Statement

Hon. Assistant Commissioner
for Patents
Washington, D.C. 20231

Sir:

The following information is submitted in
compliance with Applicants' duty of disclosure under 37
CFR § 1.56. A copy of each reference is enclosed.

U.S. Patents

<u>Pat. No.</u>	<u>Patentee</u>	<u>Grant Date</u>
5,067,805	Corle et al.	11/26/91
5,486,701	Norton et al.	01/23/96
5,517,312	Finarov	05/14/96
5,604,344	Finarov	02/18/97
5,608,526	Piwonka-Corle et al.	03/04/97
5,682,242	Eylon	10/28/97
5,747,813	Norton et al.	05/05/98
5,859,424	Norton et al.	01/12/99
5,885,045	Rush	03/23/99
5,889,593	Bareket	03/30/99
5,943,122	Holmes	08/24/99
5,957,749	Finarov	09/28/99
5,991,022	Buermann et al.	04/27/99

Foreign Patent Document

<u>Doc. No.</u>	<u>Country</u>	<u>Publ. Date</u>
EP 0973068 A2	EPO	01/19/2000
EP 0973069 A2	EPO	02/19/2000

Other Reference

Nanometrics News Release, "Applied Materials/Nanometrics Sign Pact For Metrology Integration", Copyright 1998 Worldwide Videotex, Electro Manufacturing, November 1998, No. 11, Vol. 11.

CERTIFICATE OF MAILING

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Asst. Commissioner for Patents, Washington, D.C. 20231

Signed: *Sally Azevedo*
Typed Name: Sally Azevedo

Date: October 29, 2001

Respectfully submitted,

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FORM PTO-1449	Atty. Docket No. SEN-002	Serial No. 09/927,102
LIST OF PRIOR ART CITED BY APPLICANT	Applicant: Michael Weber-Grabau et al.	
	Filing Date: August 10, 2001	Group: 2877

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Grant Date	Name	Class	Sub Class	Filing Date
AA	5,067,805	11/26/91	Corle et al.	359	235	
AB	5,486,701	01/23/96	Norton et al.	250	372	
AC	5,517,312	05/14/96	Finarov	356	386	
AD	5,608,526	03/04/97	Piwonka-Corle et al.	356	369	
AE	5,682,242	10/28/97	Eylon	356	401	
AF	5,747,813	05/05/98	Norton et al.	250	372	
AG	5,859,424	01/12/99	Norton et al.	250	226	
AH	5,885,045	03/23/99	Rush	414	417	
AI	5,889,593	03/30/99	Bareket	356	445	
AJ	5,943,122	08/24/99	Holmes	356	73	

FOREIGN PATENT DOCUMENTS

Examiner Initial*	Document Number	Grant Date	Country	Class	Sub Class	Translation Yes No
AK	EP0973068		EPO			X
AL	EP0973069		EPO			X

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AM	Nanometrics News Release, "Applied Materials/Nanometrics Sign Pact For Metrology Integration", Copyright 1998 Worldwide Videotex, Electro Manufacturing, Nov. 1998, No. 11, Vol. 11.
AN	
AO	

EXAMINER:	DATE CONSIDERED:
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*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



FORM PTO-1449

Atty. Docket No.
SEN-002Serial No.
09/927,102LIST OF PRIOR ART
CITED BY APPLICANTApplicant:
Michael Weber-Grabau et al.Filing Date:
August 10, 2001Group:
2877

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Grant Date	Name	Class	Sub Class	Filing Date
BA	5,957,749	09/28/99	Finarov	451	6	
BB	5,991,022	04/27/99	Buermann et al.	356	319	
BC						
BD						
BE						
BF						
BG						
BH						
BI						
BJ						

FOREIGN PATENT DOCUMENTS

Examiner Initial*	Document Number	Grant Date	Country	Class	Sub Class	Translation Yes No
BK						
BL						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

BM	
BN	
BO	

EXAMINER:

DATE CONSIDERED:

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